



News Release: Plasma-Therm Releases Latest Generation Mask Etcher: The MLS

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St. Petersburg, FL -- Plasma-Therm, a global supplier of plasma process equipment, is pleased to announce the release of the latest product in the Mask Etcher series: Mask Etcher MLS.

Mask Etcher MLS, where MLS stands for Manual Load System, will allow photomask manufacturers to smoothly transition from wet etch capabilities to a more advanced dry etch performance. The MLS allows for etch of 250 to 180 nm technology nodes. The concept, design and implementation of the MLS will also allow for system upgradeability all the way down to 90nm technology node.

“The MLS will support wet etch technology users in the photomask industry as they transition to dry etch technologies,” stated Ed Ostan, executive vice president of sales & marketing. “We want to be a key business partner for our customers and offer simple and cost effective opportunities to expand as their needs and technological requirements grow.”

Plasma-Therm, founded in 1974, is a supplier of advanced plasma process equipment that caters to various specialty markets including photomask, solid state lighting, thin film head and compound semiconductor. Plasma-Therm offers both dry etch & PECVD technologies. Plasma-Therm has the largest worldwide install base of mask etch equipment.

For more information, please contact Kristina Martinez, marketing assistant at Plasma-Therm, at Kristina.Martinez@PlasmaTherm.com or (727) 577-4999 ext. 1308.

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